## **CLAIMS**

## WHAT IS CLAIMED IS:

- 1. A copper foil for lamination to a dielectric substrate, the copper foil comprising: said copper foil being coated with a laser ablation inhibiting layer having an average reflectivity value of at least 40 that is effective to provide a lamination peel strength to FR-4 of at least 4.5 pounds per inch.
- 2. The copper foil of claim 1 wherein the average reflectivity value is between 50 and 90.
- 3. The copper foil of claim 1 wherein said laser ablation inhibiting layer comprises nodules having an average height of less than 1.2 microns.
- 4. The copper foil of claim 3 wherein said nodules have an average height of from 0.3 micron to 1.0 micron.
- 5. The copper foil of claim 2 wherein said laser ablation inhibiting layer is a codeposited mixture of chromium and zinc and their oxides.
- 6. The copper foil of claim 4 wherein said laser ablation inhibiting layer is a codeposited mixture of chromium and zinc and their oxides.
- 7. The copper foil of claim 2 wherein said laser ablation inhibiting layer is mixture of a metal and a metal oxide and said metal oxide is selected from the group consisting of oxides of chromium, tungsten and molybdenum.
- 8. The copper foil of claim 4 wherein said laser ablation inhibiting layer is mixture of a metal and a metal oxide and said metal oxide is selected from the group consisting of oxides of chromium, tungsten and molybdenum.

- 9. An electrically conductive circuit, comprising:
- a dielectric substrate having opposing first and second sides;

a first copper foil layer laminated to a first side thereof, said copper foil coated with a laser ablation inhibiting layer having an average reflectivity value of at least 40 that is effective to provide a lamination peel strength to FR-4 of at least 4.5 pounds per inch;

said dielectric layer having a via extending therethrough and terminating at an interface between said dielectric layer and said first copper foil layer.

- 10. The electrically conductive circuit of claim 9 wherein the average reflectivity value of said laser ablation inhibiting layer is between 50 and 90.
- 11. The electrically conductive circuit of claim 10 wherein said laser ablation inhibiting layer comprises nodules having an average height of from 0.3 micron to 1.0 micron.
- 12. The copper foil of claim 11 wherein said laser ablation inhibiting layer is a codeposited mixture of chromium and zinc and their oxides.
- 13. The copper foil of claim 11 wherein said laser ablation inhibiting layer is mixture of a metal and a metal oxide and said metal oxide is selected from the group consisting of oxides of chromium, tungsten and molybdenum.
- 14. The copper foil of claim 11 wherein said dielectric substrate is selected from the group consisting of glass reinforced epoxy and polyimide.
  - 15. A method for the manufacture of a printed circuit, comprising the steps of:
- (a) coating a copper foil with a laser ablation inhibiting layer that is effective to provide a reflectivity value of at least 40 to said coated copper foil and that is effective to provide a lamination peel strength to FR-4 of at least 4.5 pounds per inch;
- (b) laminating said at least a first layer of said coated copper foil to a first side of a dielectric substrate;
  - (c) forming said first layer into a plurality of circuit traces; and
- (d) either before or after step (c) forming at least one via through said dielectric substrate to an interface with said first layer.

- 16. The method of claim 15 wherein said via is formed by laser ablation.
- 17. The method of claim 16 wherein said step (a) is effective to form said laser ablation inhibiting layer with an average surface roughness ( $R_z$ ) of less than 1.0  $\mu$ m and with nodules having an average height of from 0.3 micron to 1.0 micron.
- 18. The method of claim 17 including selecting said laser ablation inhibiting layer from the group consisting of a codeposited mixture of chromium, zinc and their oxides, and a mixture of a metal and a metal oxide where said metal oxide is selected from the group consisting of oxides of chromium, tungsten and molybdenum.
- 19. The method of claim 18 including depositing a laser ablation enhancing layer on a side of said copper foil opposite said interface.
- 20. The method of claim 18 including laminating a second layer of said coated copper foil to an opposing second side of a dielectric substrate, forming said second layer into a plurality of circuit traces and forming said at least one via through both second layer and said dielectric substrate to an interface with said first layer.